

heating and rapid cooling, cannot be done well and homogeneous amorphous surface could not be obtained.

#### EXAMPLE 9

Pulse duration was varied and in case the duration was shorter than  $0.5 \mu\text{s}$ , the microcracks were observed on the surface of metal and/or partial metal dentures, so the corrosion resistance decreases essentially. And in case, the duration is over than  $10 \mu\text{s}$ , the non-homogeneous surface could be obtained. This relation is summarized as

$$\tau \approx k \cdot r^2 / a, \quad (1)$$

where  $r$  is an extrapolated penetration depth of the electrons in material,  $a = \lambda / \rho \cdot c$  is thermal diffusivity,  $\lambda$ ,  $\rho$ ,  $c$  are thermal conductivity, density, and heat capacity, respectively. For most of materials the value of  $a$  belongs to the range from  $0.06$  (for Ti) to  $1.12 \text{ cm}^2/\text{s}$  (for Cu). Concerning the value of  $r$ , it belongs to the range (at electrons energy  $20\text{--}40 \text{ keV}$ ) from  $0.5\text{--}1.3 \mu\text{m}$  (for W) to  $3.3\text{--}9.3 \mu\text{m}$  (for Al), correspondingly.

The coefficient  $k$  depends on the material properties, namely it is defined by the relation between  $a$  and  $r$ . To provide a high efficiency of the surface heating, from one hand, and to decrease the thermal stresses defined by the temperature gradients in a surface layer from other hand, value of  $k$  is chosen by the following way:

- a) for most of constructive metallic alloys (alloys on the base of Fe, Al, and Ti), the coefficient  $k \approx 1\div 5$ .
- b) In case of the materials having high temperature conductivity and for small value of penetration depth  $r$  (Cu, Mo, W and alloys based on them) the coefficient  $k$  should be equal  $k \approx 10\div 50$ .

Using the Eq. 1 and taking into account the limitations of  $k$  one can obtain the range of the beam pulse duration  $\tau \approx 0.5\div 10 \mu\text{s}$

What is claimed is:

1. Pulsed Electron Beam System to use for the surface modification of the metal and/or partial metal dentures. The system is consisted with an explosive emission cathode, accelerating gap formed by the cathode and plasma anode, and an electron collector where the metal and/or partial metal dentures are fixed, which are placed into a guide magnetic field. The holder of the metal and/or partial metal dentures is made with metal materials offering cooling effect to the mentioned products.
2. The process to modify the surface of the metal and/or partial metal dentures using Pulsed Electron Beam Systems, the irradiated energy should be over than  $0.1 \text{ J/cm}^2$  and the pulse repetition is lower than 100.
3. The metal and/or partial metal dentures which surface is modified using pulsed electron beam irradiation for polishing from as-cast to finished and corrosion resistance modified products.